

| L Number | Hits | Search Text | DB | Time stamp |
|----------|-------|--|---|------------------|
| - | 9844 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$4)).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:44 |
| - | 10015 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$45)).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/10/01 07:54 |
| - | 7329 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$45)).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/10/01 07:57 |
| - | 10011 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$5)).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/10/01 07:57 |
| - | 733 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$5)).clm.) and capacit\$5.clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/10/01 07:57 |
| - | 264 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$5)).clm.) and capacit\$5.clm.) and electrode.clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/10/01 07:57 |
| - | 53 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$5)).clm.) and capacit\$5.clm.) and electrode.clm.) and (concentration impurity purity) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:36 |
| - | 17 | ((diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) near2 (conduct\$5)).clm.) and capacit\$5.clm.) and electrode.clm.) and (concentration impurity purity).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:28 |
| - | 700 | (216/2).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:36 |
| - | 92 | ((216/2).CCLS.) and impurit\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:37 |
| - | 1 | ((216/2).CCLS.) and impurit\$4 near3 concentration) and etch near1 pit | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:39 |
| - | 1 | ((216/2).CCLS.) and impurit\$4 near3 concentration) and etch near1 pit) and diaphragm | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:39 |

| | | | | |
|---|-------|---|---|------------------|
| - | 23 | ((216/2).CCLS.) and impurit\$4 near3 concentration | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:41 |
| - | 20 | ((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:48 |
| - | 15 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:32 |
| - | 3 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and etch near3 (pit hole groove dip) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:26 |
| - | 3 | ((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch near3 (pit hole groove dip) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:49 |
| - | 2 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and electrode near3 dielectric near3 (film layer support substrate cover\$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:57 |
| - | 1 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and electrode near3 dielectric near3 (film layer support substrate cover\$4)) and pressure | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:55 |
| - | 1 | ((((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and electrode near3 dielectric near3 (film layer support substrate cover\$4)) and pressure) and silicon | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 18:55 |
| - | 11 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and pressure | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:04 |
| - | 6 | (((((216/2).CCLS.) and impurit\$4 near3 concentration) and etch) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5)) and pressure near3 (sens\$4 measur\$3 detect test transducer gauge monitor evaluate estimat\$4 identif\$4 indicat\$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:27 |
| - | 44167 | impurit\$4 near3 concentration | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:27 |
| - | 1092 | ((impurit\$4 near3 concentration) and pressure near3 (sens\$4 measur\$3 detect test transducer gauge monitor evaluate estimat\$4 identif\$4 indicat\$4)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:29 |
| - | 18 | ((impurit\$4 near3 concentration) and pressure near3 (sens\$4 measur\$3 detect test transducer gauge monitor evaluate estimat\$4 identif\$4 indicat\$4)) and etch near3 (pit groove hole dip) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:30 |

| | | | | |
|---|----|---|---|------------------|
| - | 13 | (((impurit\$4 near3 concentration) and pressure near3 (sens\$4 measur\$3 detect test transducer gauge monitor evaluate estimat\$4 identif\$4 indicat\$4)) and etch near3 (pit groove hole dip)) and (diaphragm membrane elastic\$5 flexible deformable elastom\$5 resilient\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/06/26 19:32 |
|---|----|---|---|------------------|